

CLAIMS

1. A resist composition comprising an alkaline soluble novolak resin, a
naphthoquinonediazide photosensitive compound and an organic solvent,
5 characterized in that the organic solvent comprises benzyl alcohol or its
derivatives.
2. The resist composition according to claim 1, characterized in that
the organic solvent comprises 1 % by weight to 35 % by weight of
10 benzyl alcohol or its derivatives.
3. A photosensitive resist composition comprising an alkaline soluble
acrylic resin or novolak resin, a strong acid or a radical generating
compound by irradiating UV ray, a crosslinker and an organic solvent,
15 characterized in that the organic solvent comprises benzyl alcohol or its
derivatives.
4. The resist composition according to claim 1, characterized in that
the organic solvent comprises 1 % by weight to 35 % by weight of
20 benzyl alcohol or its derivatives.
5. An organic solvent for removing a resist, comprising benzyl alcohol
or its derivatives.